

Innovative strategies for improved test measurements using Kelvin contacts with a Flying prober

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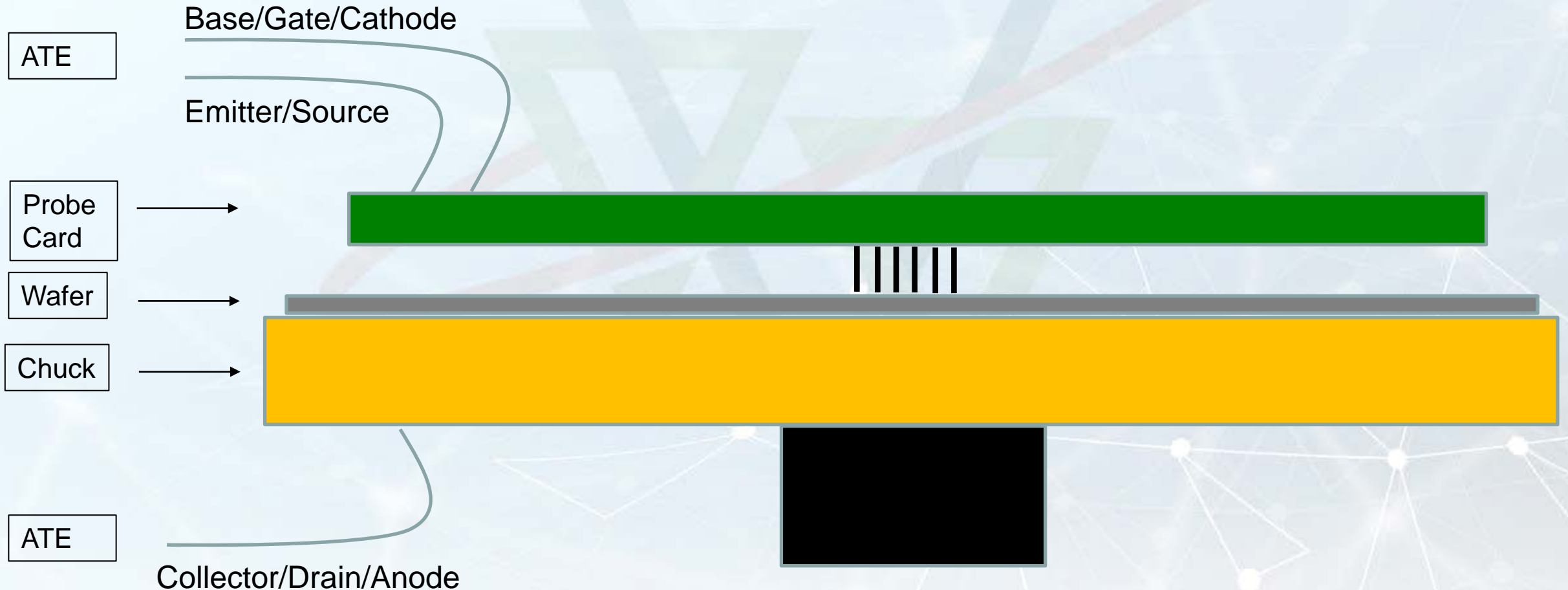
PROBE TODAY, FOR TOMORROW

Overview

- **Current probing Power Devices at wafer level Architecture**
- **Physical limit of probing on discrete power devices**
- **Tomorrow needs on discrete power device applications**
- **Double sided Kelvin contacts architecture**
- **STMicroelectronics field experience**
- **Summary**

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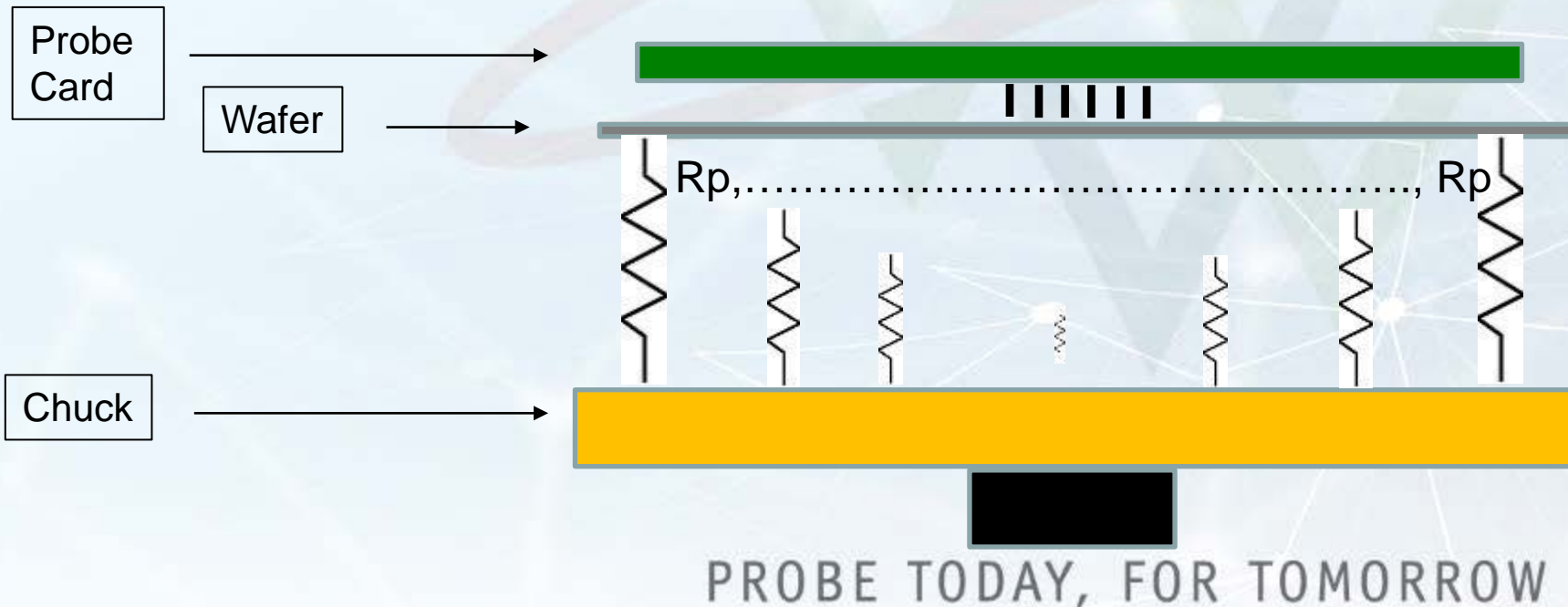
Current probing Power Devices at wafer level Architecture



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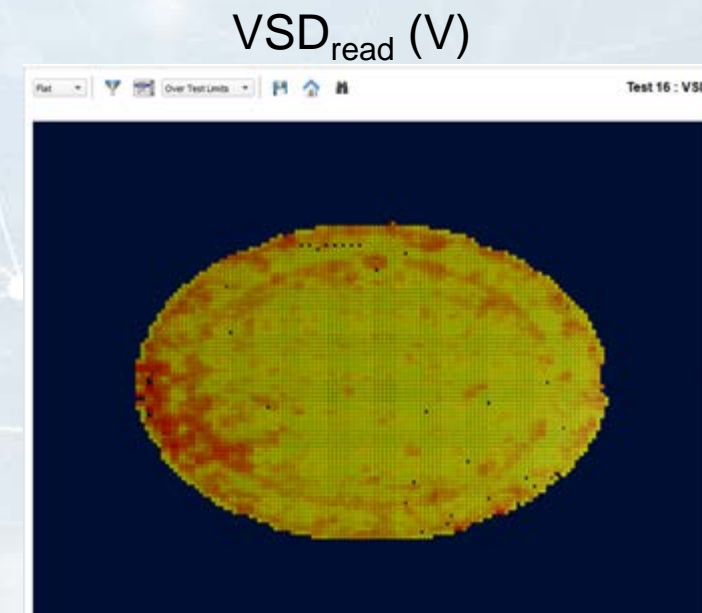
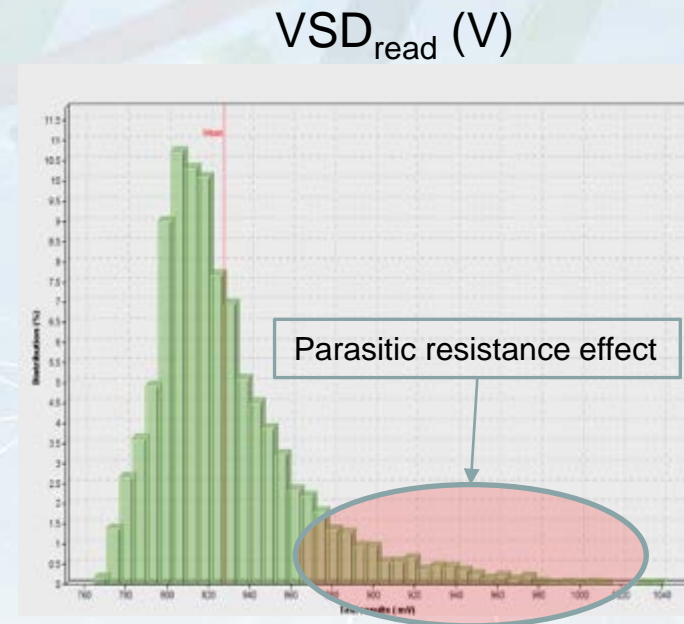
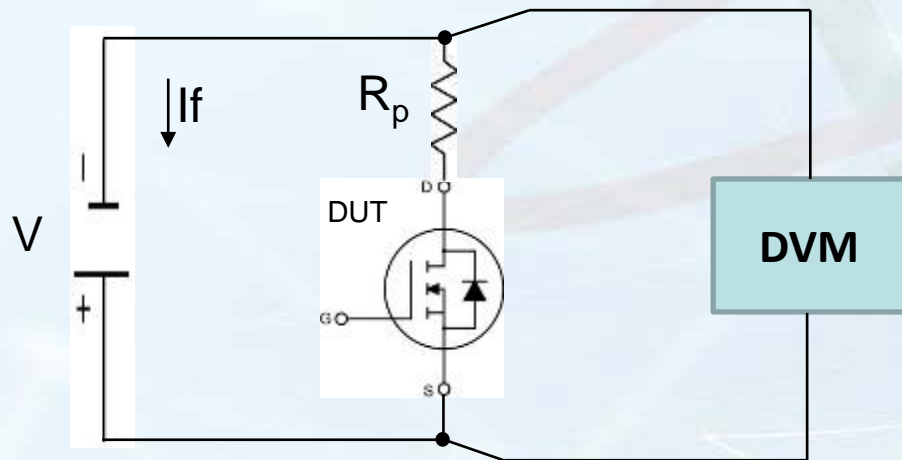
Physical limit of probing on discrete power devices

- There is NOT a uniformly distributed parasitic resistance between the wafer backside and the chuck top
- Parasitic resistance affects the conduction measurement on Power discrete devices (Diode, MOSFET, IGBT)



Physical limit of probing on discrete power devices

- Effects on electrical measurement readings of a not-uniform parasitic resistance among all the wafer backside on conduction tests (i.e.: VSD)



R_p = Parasitic resistance
 $VSD_{read} = VSD_{real} + (R_p * I_f)$

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Tomorrow needs on discrete power device applications

- **Bare die for hybrid module is the today and tomorrow business for**
 - Industrial application
 - Automotive application
 - Vehicle electrification
- **To guarantee as much as possible the real electrical measurements in conduction (high current) it is essential to eliminate the parasitic resistance of the conventional probing solutions**

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Double sided Kelvin contacts architecture

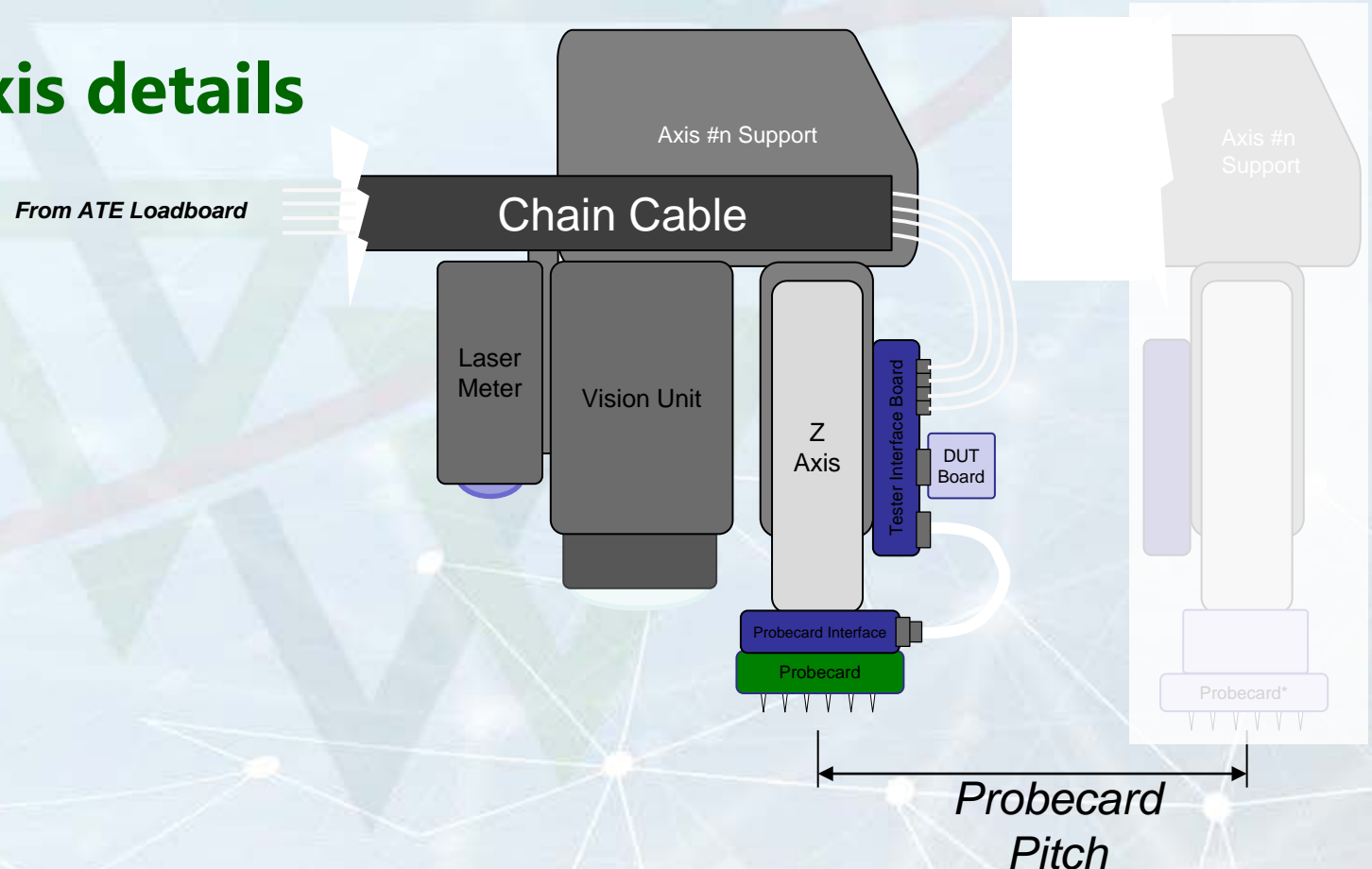


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Double sided Kelvin contacts architecture

- **Spea Flying prober Axis details**

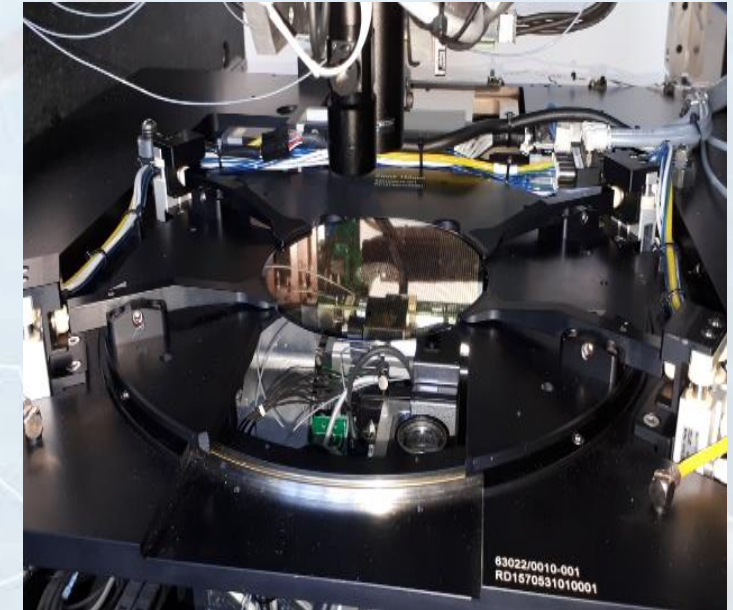
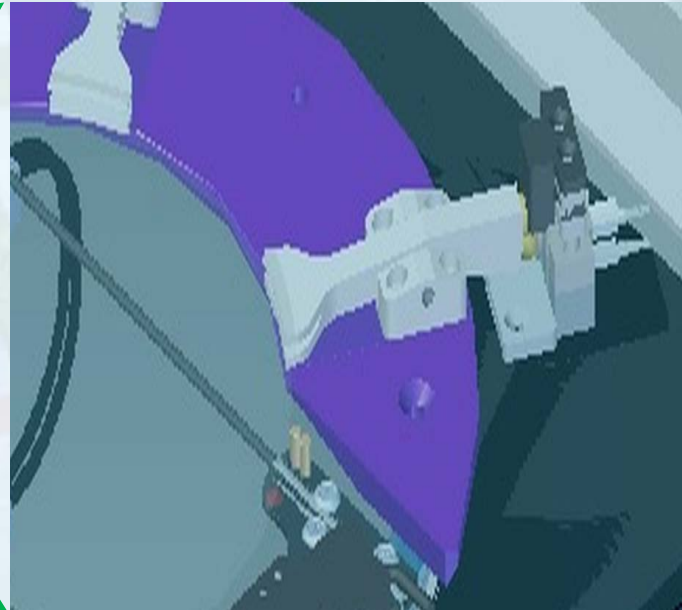
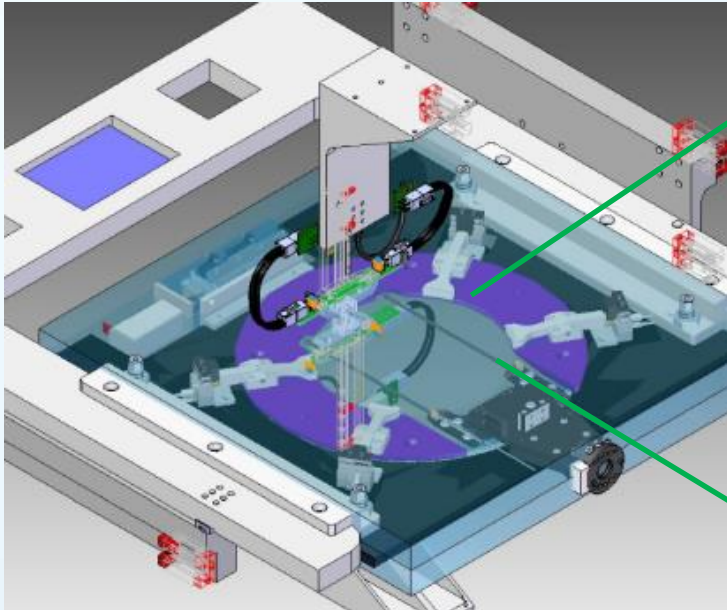
- Full motion X,Y,Z
- LASER autofocus
- Vision unit
 - Pattern recognition
 - Wafer alignment
 - Probe card alignment
- DUT board
- Probe card holder



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Double sided Kelvin contacts architecture

- Mechatronic wafer handling/Chuck holder for 6"/ 8" wafer



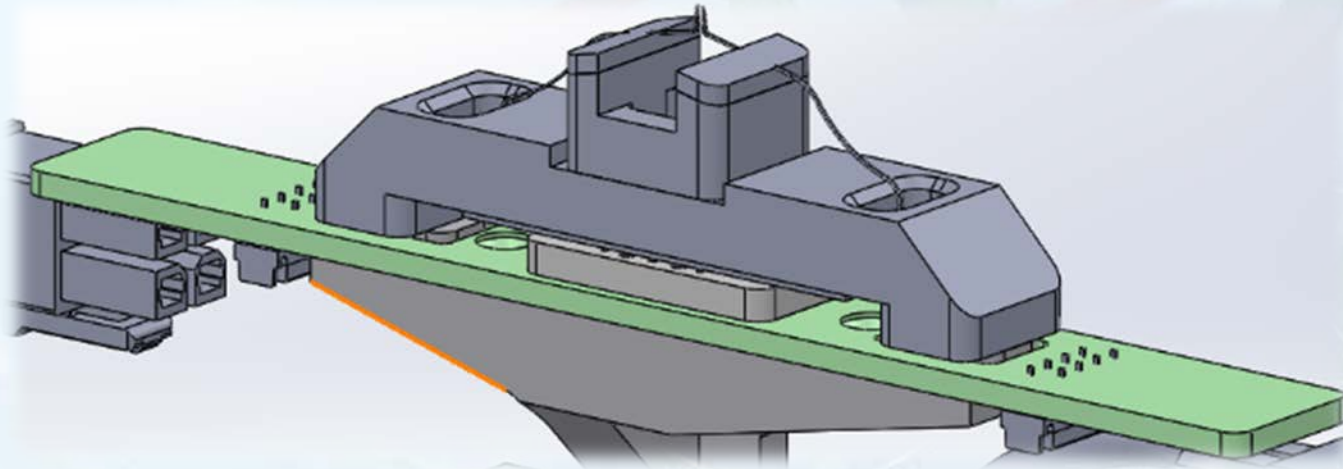
- Chuck holder based on clamp over exclusion edge area of the wafer

Double sided Kelvin contacts architecture

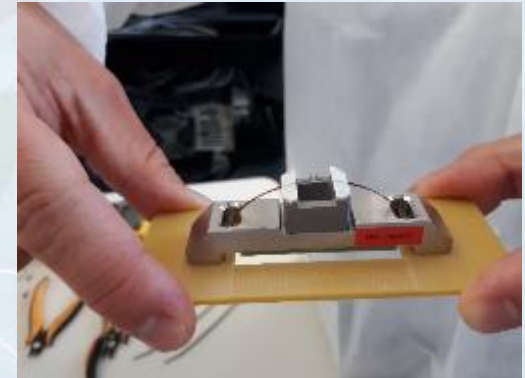
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- **Technoprobe probe card**

- New electro mechanical interface has been designed to support Top and Bottom coupled probe heads



Probe card architecture



Probe Card with cantilever tips



Probe card electrical/mechanical interface

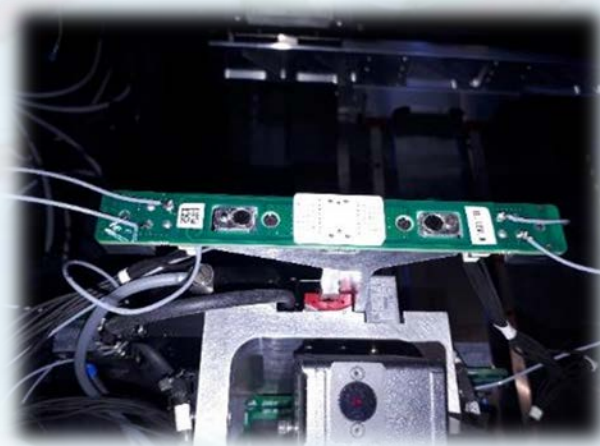
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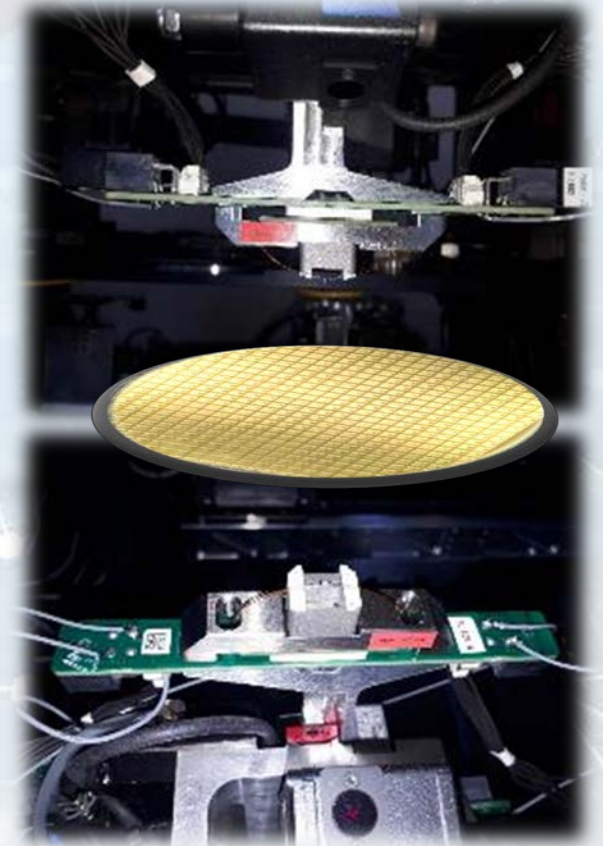
Double sided Kelvin contacts architecture

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- **Custom mechanical and electrical connection the probe cards**
 - Top and bottom probe cards are coupled on same axis to contact devices from top and bottom of the wafer



Axis electrical/mechanical coupling



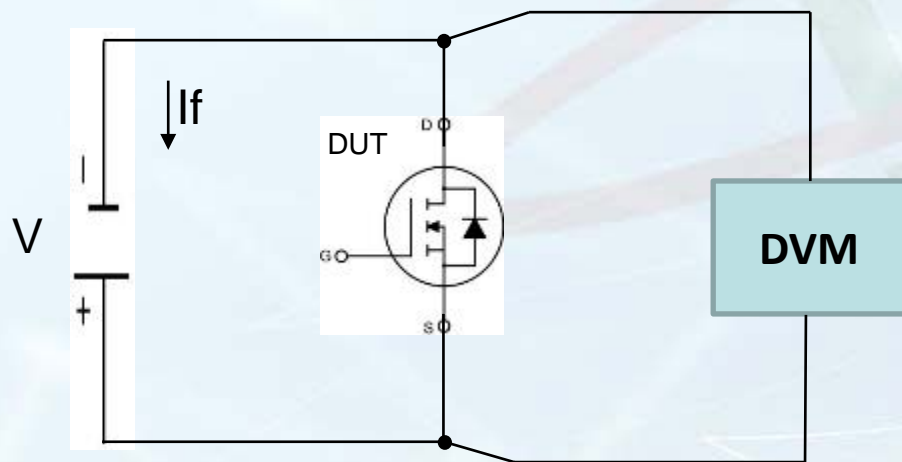
Top-Bottom Probe Cards coupled on axis

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STMicroelectronics field experience

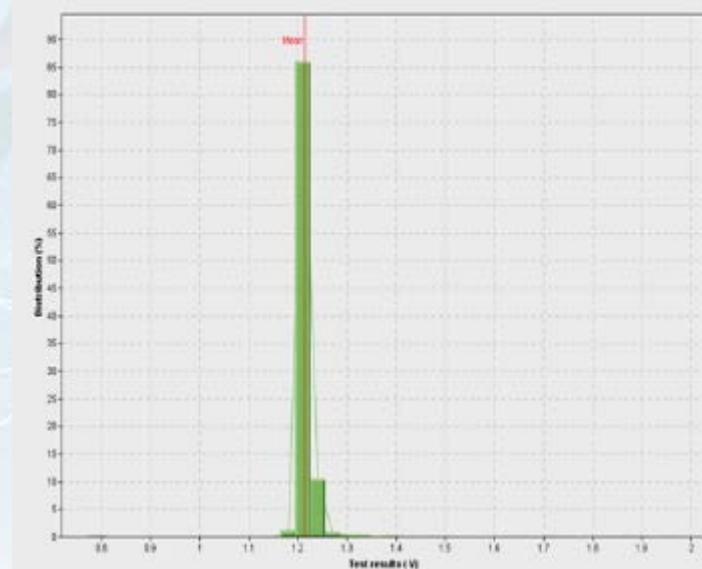
- Parasitic resistance throughout all surface of the wafer backside is dramatically minimized thanks to the double sided Kelvin contact probing resulting in very narrow VSD_{read} distribution



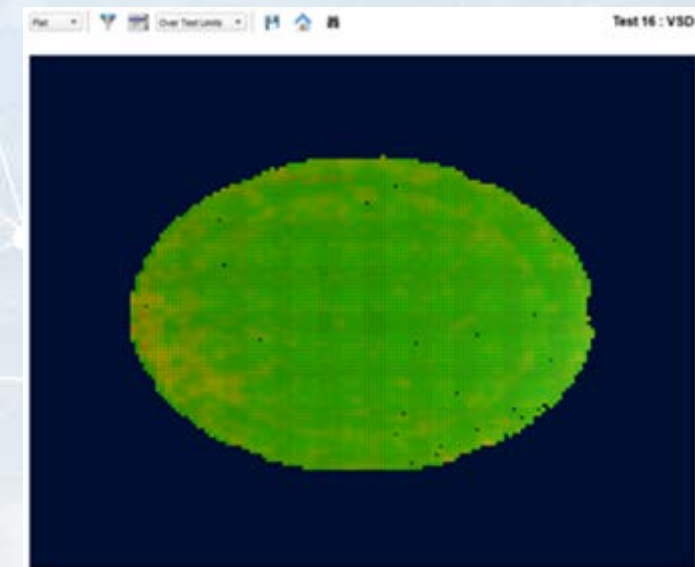
$$VSD_{read} = VSD_{real} + (R_p * I_f)$$

- Note: $R_p \sim 0\Omega$

VSD_{read} (V)



VSD_{read} (V)



PROBE TODAY, FOR TOMORROW

STMicroelectronics field experience



The test cell development has been achieved in collaboration **STMicroelectronics, SPEA, Mechatronic and Technoprobe**

This specific application has been released to production in order to increase Test capacity for Automotive Power Discrete products

in STMicroelectronics EWS (Tours, France site)

PROBE TODAY, FOR TOMORROW

Project Team Members

STMicroelectronics

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SPEA

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Mechatronic

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Hermann HIDEN	Technical Account Manager

Technoprobe

Alessandro ANTONIOLI	Senior Director Business Development and Marketing
Tommaso MASI	Technical Sales Manager

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Project Team Members

Thanks to all the team members for the outstanding project success !



Brainstorming session with all the different organizations

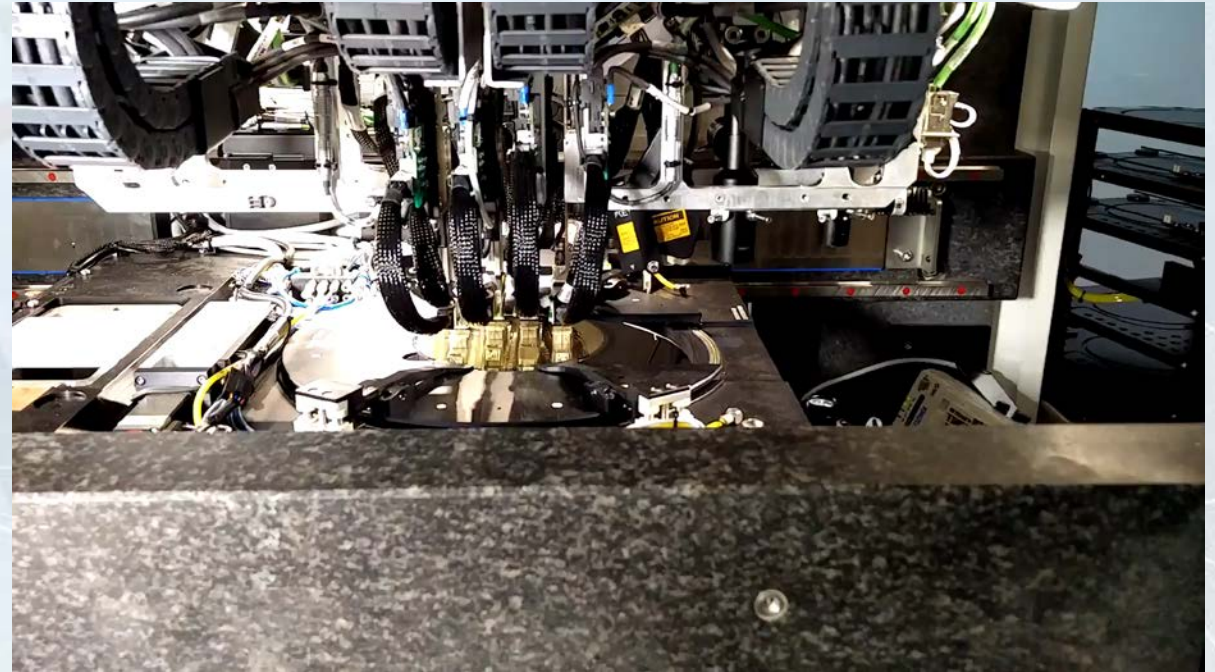


Tours team in front of the tool

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Summary/Conclusion

- The innovative strategies implemented in this very first equipment prototype, double sided Flying Prober, gives the opportunity to perform a very accurate electrical conduction measurement
- This architecture opens new opportunities in the domain of Bare Die and KGD business
- Here a 20" video showing the implemented double side Kelvin contacts probing performance



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The background features a light blue gradient with several overlapping geometric shapes: a large blue triangle, a green triangle, and a red ring. A network of white lines with small yellow nodes is visible in the lower right quadrant.

Thanks

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